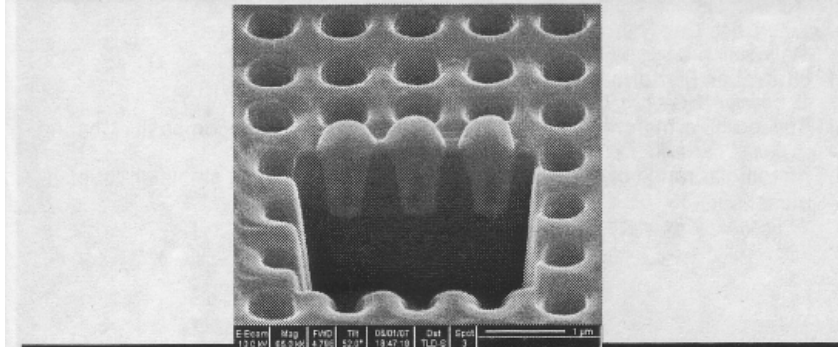


MO82.109 Design and implementation of silicon-based optical nanostructures for integrated photonic circuit applications using Deep Reactive Ion Etching (DRIE) technique

S. Selvarasah, R. Banyal, B.D.F. Casse, W.T. Lu, S. Sridhar, M.R. Dokmeci, Northeastern University, US, Vol. 3, pp. 54



MO82.109 SEM of cross section of 803nm deep and 500nm wide holes.